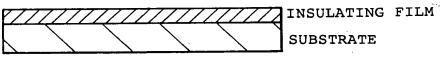
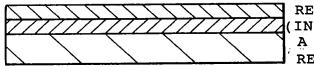
FORMATION OF INSULATING FILM (COATING/BAKING)

Fig.1A



RESIST COATING/PRE-BAKING

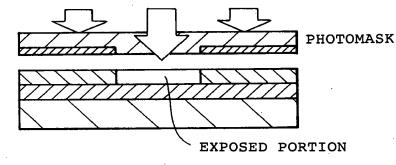
Fig.1B



RESIST
(IN THE CASE OF
A POSITIVE
RESIST)

MASK ALIGNMENT/EXPOSURE:

Fig.1C



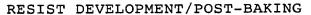
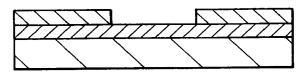
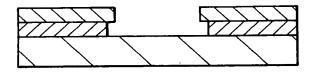


Fig.1D



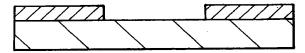
INSULATING FILM ETCHING

Fig.1E



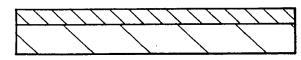
RESIST ASHING

Fig.1F



POLYSILAZANE COATING

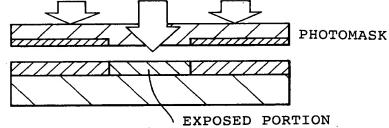
Fig.2A



MASK ALIGNMENT/EXPOSURE

POLYSILAZANE

Fig.2B



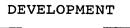


Fig.2C

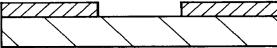


Fig.2D

